

We Claim:

1 1. An arc chamber of an ion implanter system comprising:
2 an arc chamber enclosure for an electron emissive source, said source extending
3 into said arc chamber enclosure through a wall of said arc chamber enclosure, said wall
4 through which said source extends comprising an insulator material surrounding said
5 source.

1 2. The arc chamber of Claim 1 wherein said insulator material is a high
2 temperature ceramic material.

1 3. The arc chamber of Claim 2 wherein said insulator material is
2 selected from the group consisting of alumina and boron nitride.

1 4. The arc chamber of Claim 3 wherein said insulator material is boron
2 nitride.

1 5. The arc chamber of Claim 1 wherein a substantial portion of said wall
2 through which said source extends into the arc chamber comprises an insulator material.